

IN THE CLAIMS

Please amend the claims as follows:

Claim 1 (Currently Amended): A rod target for an arc evaporation source, said rod target employing its outer peripheral surface as an evaporation surface, wherein the opposite ends of said rod target in the longitudinal direction of said rod target are each formed thicker than the central part of said rod target, wherein a taper portion is provided in a boundary portion between the thicker portion at each of the opposite ends of said rod target in the longitudinal direction of said rod target and the narrower portion in the central part of said rod target so that the diameter of said rod target gradually decreases from each of the thicker portions toward the narrower portion, wherein a tilt angle of the taper portion is set to be not less than 3 degrees nor more than 30 degrees.

Claim 2 (Currently Amended): ~~[[The]]~~ A rod target for an arc evaporation source according to Claim 1, said rod target employing its outer peripheral surface as an evaporation surface, wherein the opposite ends of said rod target in the longitudinal direction of said rod target are each formed thicker than the central part of said rod target, wherein the length of the thicker portion at each of the opposite ends of said rod target in the longitudinal direction of said rod target is set to be not less than 75 mm nor more than 200 mm.

Claim 3 (Currently Amended): ~~[[The]]~~ A rod target for an arc evaporation source according to Claim 1, said rod target employing its outer peripheral surface as an evaporation surface, wherein the opposite ends of said rod target in the longitudinal direction of said rod target are each formed thicker than the central part of said rod target, wherein the ratio of the effective consumed sectional area of the thicker portion at each of the opposite ends of said rod target in the longitudinal direction of said rod target with respect to the effective

consumed sectional area of the narrower portion in the central part of said rod target is set to be more than 1.0 and not more than 3.0.

Claim 4 (Currently Amended): ~~[[The]]~~ A rod target for an arc evaporation source according to Claim 1, said rod target employing its outer peripheral surface as an evaporation surface, wherein the opposite ends of said rod target in the longitudinal direction of said rod target are each formed thicker than the central part of said rod target, wherein [[the]] a boundary portion between the thicker portion at each of the opposite ends of said rod target in the longitudinal direction of said rod target and the narrower portion in the central part of said rod target is changed in the thickness in a step-by-step manner so that the thickness of said rod target gradually decreases from the thicker portion at each of the opposite ends of said rod target in the longitudinal direction of said rod target toward the narrower portion in the central part of said rod target.

Claims 5-6 (Cancelled).

Claim 7 (Currently Amended): A method for manufacturing said rod target for an arc evaporation source ~~as recited in Claim 1,~~ said rod target employing its outer peripheral surface as an evaporation surface, wherein the opposite ends of said rod target in the longitudinal direction of said rod target are each formed thicker than the central part of said rod target, comprising integrally assembling the thicker portion at each of the opposite ends of said rod target in the longitudinal direction of said rod target and the narrower portion in the central part of said rod target, after, at least, separately producing the thicker portion at each of the opposite ends of said rod target in the longitudinal direction of said rod target and the narrower portion in the central part of said rod target.

Claim 8 (Original): An arc deposition device in which a rod target for an arc evaporation source and work are provided in a vacuum vessel, in which a target material is evaporated from the outer peripheral surface of the rod target for an arc evaporation source, and in which the evaporated target material is caused to adhere to the work, wherein the rod target for an arc evaporation source as recited in Claim 1 is used as the rod target for an arc evaporation source provided in the vacuum vessel.

Claim 9 (New): An arc deposition device in which a rod target for an arc evaporation source and work are provided in a vacuum vessel, in which a target material is evaporated from the outer peripheral surface of the rod target for an arc evaporation source, and in which the evaporated target material is caused to adhere to the work, wherein the rod target for an arc evaporation source as recited in Claim 2 is used as the rod target for an arc evaporation source provided in the vacuum vessel.

Claim 10 (New): An arc deposition device in which a rod target for an arc evaporation source and work are provided in a vacuum vessel, in which a target material is evaporated from the outer peripheral surface of the rod target for an arc evaporation source, and in which the evaporated target material is caused to adhere to the work, wherein the rod target for an arc evaporation source as recited in Claim 3 is used as the rod target for an arc evaporation source provided in the vacuum vessel.

Claim 11 (New): An arc deposition device in which a rod target for an arc evaporation source and work are provided in a vacuum vessel, in which a target material is evaporated from the outer peripheral surface of the rod target for an arc evaporation source,

and in which the evaporated target material is caused to adhere to the work, wherein the rod target for an arc evaporation source as recited in Claim 4 is used as the rod target for an arc evaporation source provided in the vacuum vessel.

Claim 12 (New): A rod target for an arc evaporation source, said rod target employing its outer peripheral surface as an evaporation surface, wherein the opposite ends of said rod target in the longitudinal direction of said rod target are each formed thicker than the central part of said rod target, wherein a taper portion is provided in a boundary portion between the thicker portion at each of the opposite ends of said rod target in the longitudinal direction of said rod target and the narrower portion in the central part of said rod target so that the diameter of said rod target gradually decreases from each of the thicker portions toward the narrower portion, wherein a tilt angle of the taper portion is predetermined to be not less than 3 degrees nor more than 30 degrees.

Claim 13 (New): A rod target for an arc evaporation source, said rod target employing its outer peripheral surface as an evaporation surface, wherein the opposite ends of said rod target in the longitudinal direction of said rod target are each formed thicker than the central part of said rod target, wherein the length of the thicker portion at each of the opposite ends of said rod target in the longitudinal direction of said rod target is predetermined to be not less than 75 mm nor more than 200 mm.